In the Claims:

1. (Currently amended) A thin-film LED comprising:

an active layer (7), which emits electromagnetic radiation (19) in a main radiation direction; [[(15),]]

a current expansion layer (9), which is disposed downstream of the active layer (7) in the main radiation direction (15) and is made of a first nitride compound semiconductor material;

[[,]] a main area (14), through which the radiation (19) emitted in the main radiation direction (15) is coupled out; [[,]] and

a first contact layer (11, 12, 13) arranged on the main area (14),

characterized in that wherein

the transverse conductivity of the current expansion layer (9) is increased by formation of a two-dimensional electron gas or hole gas.

2. (Currently amended) The thin-film LED as claimed in claim 1, eharacterized in that wherein

in order to form a two-dimensional electron or hole gas in the current expansion layer (9), at least one layer (10) made of a second nitride compound semiconductor material having a larger electronic band gap than the first nitride compound semiconductor material is embedded in the current expansion layer (9).

3. (Currently amended) The thin-film LED as claimed in claim 2, eharacterized in that wherein

a plurality of layers (10a, 10b, 10e) made of the second nitride compound semiconductor material are embedded in the current expansion layer (9).

4. (Currently amended) The thin-film LED as claimed in claim 2 or 3, eharacterized in that wherein

the number of layers (10a, 10b, 10c) made of the second nitride compound semiconductor material is between 1 and 5 inclusive.

5. (Currently amended) The thin-film LED as claimed in claim 2, one of claims 2 to 4,

characterized in that wherein

the at least one layer (10) made of the second nitride compound semiconductor material has a thickness of 10 nm to 100 nm.

6. (Currently amended) The thin-film LED as claimed in <u>claim 2</u>, one of claims 2 to 5,

characterized in that wherein

the first nitride compound semiconductor material is GaN.

7. (Currently amended) The thin-film LED as claimed in <u>claim 2</u>, one of claims 2 to 6,

characterized in that wherein

the second nitride compound semiconductor material is $Al_xGa_{1-x}N$ where $0.1 \le x \le 0.2$.

8. (Currently amended) The thin-film LED as claimed in claim 2, one of claims 2 to 7,

characterized in that wherein

the at least one layer (10) made of the second nitride compound semiconductor material has a doping, the dopant concentration being higher in the regions adjoining the current expansion layer (9) than in a central region of the layer (10).

9. (Currently amended) The thin-film LED as claimed in <u>claim 2</u>, one of claims 2 to 8,

characterized in that wherein

the first and second nitride compound semiconductor materials are in each case n-doped.

10. (Currently amended) The thin-film LED as claimed in claim 2, one of claims 2 to 9,

characterized in that wherein

the first nitride compound semiconductor material is p-doped and the second nitride compound semiconductor material is n-doped.

11. (Currently amended) The thin-film LED as claimed in claim 1, one of the preceding claims,

characterized in that wherein

the active layer (7) has includes $In_xAl_yGa_{1-x-y}N$ where $0 \le x \le 1$, $0 \le y \le 1$ and $x + y \le 1$.

12. (Currently amended) The thin-film LED as claimed in claim 1, one of the preceding claims,

characterized in that wherein

at least one edge length of the main area (14) is 400 µm or more.

at least one edge length of the main area (14) is 800 µm or more.

13. (Currently amended) The thin-film LED as claimed in claim 12, characterized in that wherein

14. (Currently amended) The thin-film LED as claimed in claim 1, one of the preceding claims,

characterized in that wherein

operation of the thin-film LED with a current intensity of 300 mA or more is provided.

15. (Currently amended) The thin-film LED as claimed in claim 1, one of the preceding claims,

characterized in that wherein

the first contact layer (11, 12, 13) comprises no aluminum.

16. (Currently amended) The thin-film LED as claimed in claim 1, one of the preceding claims,

characterized in that wherein

less than 15% of the total area of the main area (14) is covered by the first contact layer (11, 12, 13).

17. (Currently amended) The thin-film LED as claimed in <u>claim 1</u>, one of the preceding claims,

characterized in that wherein

the first contact layer (11, 12, 13) has a lateral structure comprising a contact area (11) and a plurality of contact webs (12, 13).

18. (Currently amended) The thin-film LED as claimed in claim 17, characterized in that wherein

the contact area (11) is surrounded by at least one frame-type contact web (13), the frame-type contact web (13) being connected to the contact area by means of at least one further contact web (12).

19. (Currently amended) The thin-film LED as claimed in claim 18, characterized in that wherein the frame-type contact web (13) has a square, rectangular or circular form.

20. (Currently amended) The thin-film LED as claimed in claim 18 or 19, characterized in that wherein the number of frame-type contact webs (13) is one, two or three.

21. (Currently amended) The thin-film LED as claimed in claim 1, one of the preceding claims,

characterized in that wherein

a second contact layer (5), which reflects the emitted radiation, is provided on a side of the active layer (7) opposite to the first contact layer (11, 12, 13), the first contact layer (11, 12, 13) having a contact area (11) and the second contact layer (5) having a cutout (18) in a region opposite the contact area (11).